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PN - JP2001096241 A 20010410
PD - 2001-04-10
PR - JP19990276295 19990929
OPD - 1999-09-29
TI - WASHING LIQUID AND WASHING METHOD OF PRECISION SUBSTRATE
IN - MORIYA JIRO; SHIBANO YUKIO; OKAZAKI SATOSHI; SUZUKI MASAYUKI; NAKATSU MASAYUKI
PA - SHINETSU CHEMICAL CO
IC - B08B3/08 ; H01L21/308

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TI - Washing/cleaning liquid for precision board such as quartz glass, adhered with contaminants such as organic material or metal, contains ozone water and hydrogen water
PR - JP19990276295 19990929
PN - JP2001096241 A 20010410 DW 200137 B08B3/08 006pp
PA - (SHIE) SHINETSU CHEM IND CO LTD
IC - B08B3/08 ;H01L21/308
AB - JP2001096241 NOVELTY - The washing/cleaning liquid comprises ozone water containing 5 ppm of ozone and hydrogen water.
- DETAILED DESCRIPTION - An INDEPENDENT CLAIM is also included for cleaning method of precision board.
- USE - For cleaning precision board containing quartz glass, mask blank, photo-mask, liquid-crystal glass substrate and optical disc board, adhered with contaminants such as organic material and metal.
- ADVANTAGE - The liquid enables effective cleaning equivalent to cleaning effect provided with ozone water alone. The usage of the liquid, eliminates necessary acid-proof and chemical-resistant installations on the board.
- (Dwg. 0/0)

OPD - 1999-09-29

AN - 2001-349448 [37]

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PD - 2001-04-10
AP - JP19990276295 19990929
IN - MORIYA JIRO; SUZUKI MASAYUKI; NAKATSU MASAYUKI; OKAZAKI SATOSHI;SHIBANO YUKIO
PA - SHIN ETSU CHEM CO LTD
TI - WASHING LIQUID AND WASHING METHOD OF PRECISION SUBSTRATE
AB - PROBLEM TO BE SOLVED: To provide a precision substrate washing liquid having high capacity to wash contaminants such as organic matter and metals for making the precision substrate highly clean with ease while dispensing with acid-resistant facilities and coping with environmental problems and to provide a precision substrat washing method.
- SOLUTION: This washing liquid is an aqueous liquid obtained by mixing ozonic water or anode water with hydrogenous water or cathod water. The ozone concentration in the ozonic water or the anode water is made to be 5 ppm or higher and the hydrogen concentration in the hydrogenous water or the cathode wat r is made to be 0.5 ppm or higher.

none

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SI - H01L21/308

- B08B3/08

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